

Molecular Dynamics Simulations > of Ion Irradiation of a Surface under an Electric Field

Wednesday 6 November 2013 11:30 (30 minutes)

I will talk about how the sputtering yield of Cu is increased in the presence of an electric field. The sputtering yield is important from the point of view of the plasma formation, and we need to be able to explain where all the neutral atoms are coming from that are needed for the plasma. The sputtering yield is used as an input parameter for e.g.

the PIC simulations, so it's good to understand what is happening there.

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Session Classification: Theory and Simulation 2 - Plasma